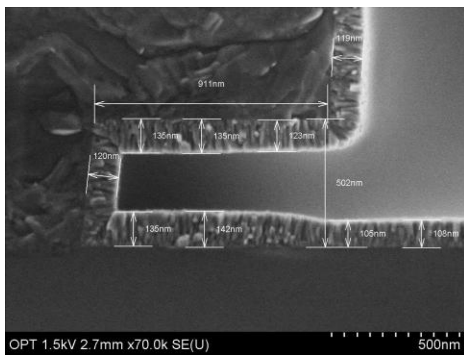
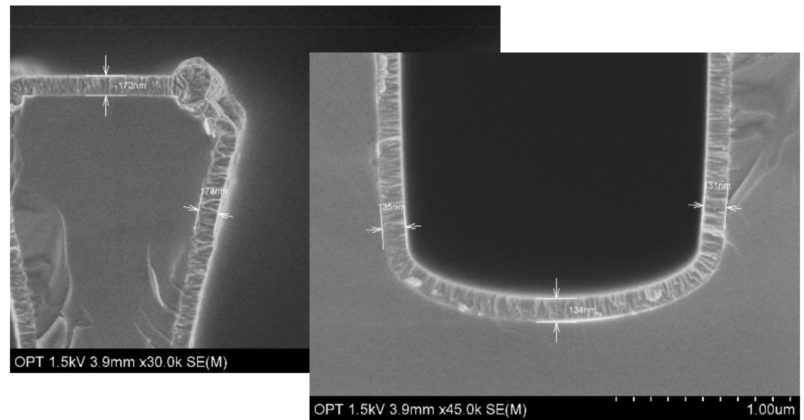
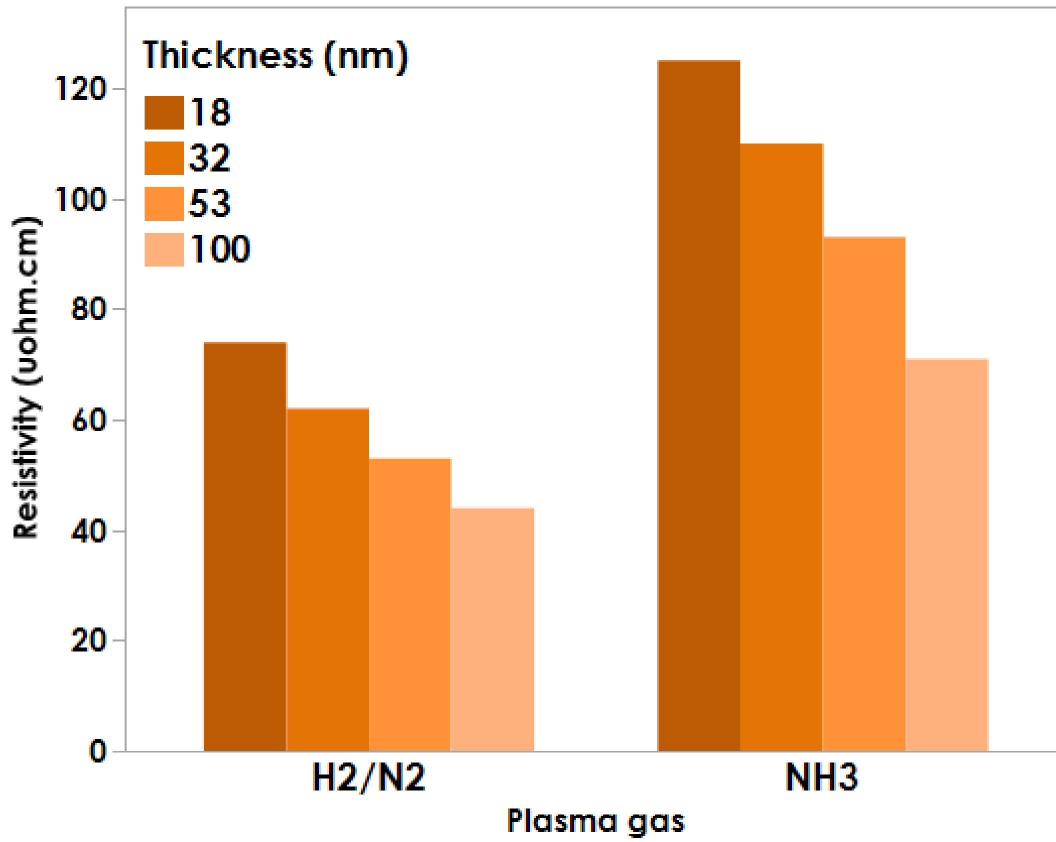
Images:



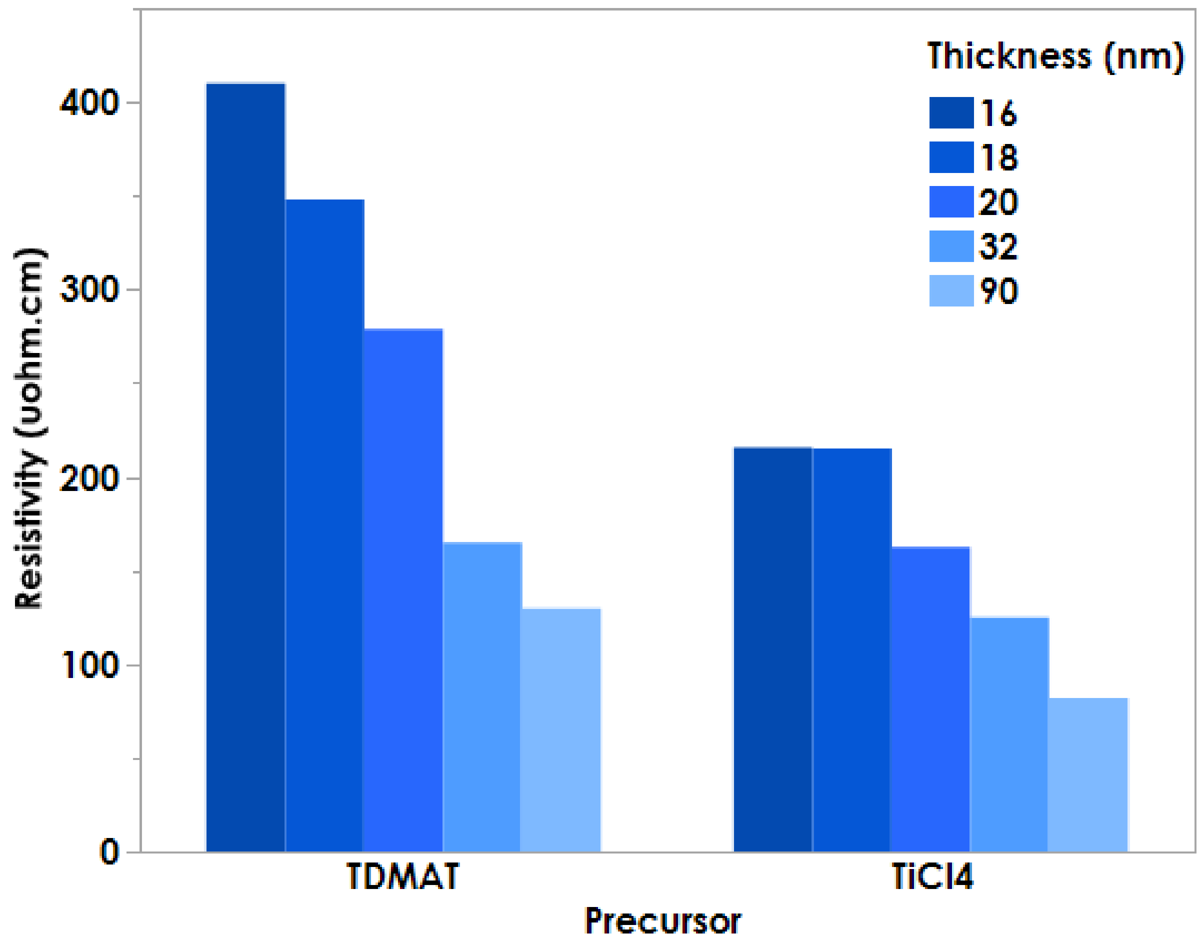
TiN conformality in 2:1 LHAR



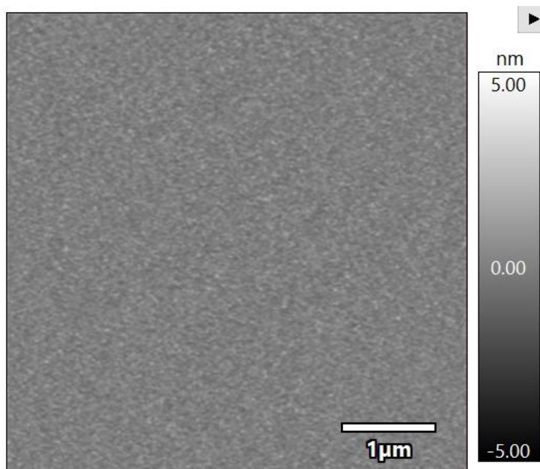
TiN conformality in 12:1 AR



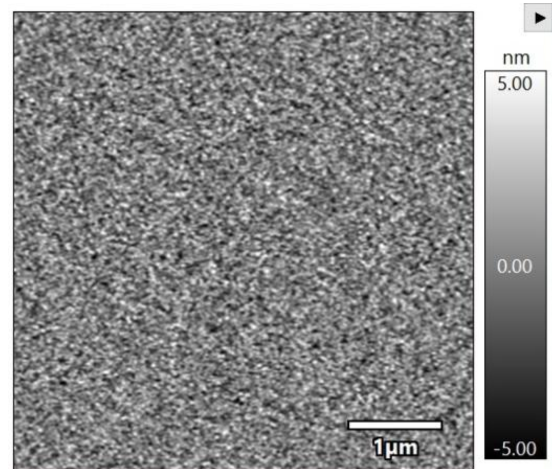
H_2/N_2 plasma gas mix yields lower resistivity



$TiCl_4$ yields lower resistivity than TDMAT



Roughness of TDMAT TiN Films is ~276 pcm



Roughness of $TiCl_4$ TiN Films is ~1.5 nm